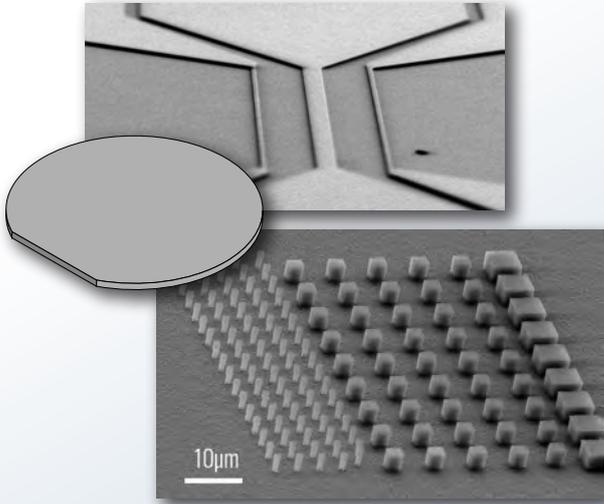


# Photolithographie

Transfert de motifs sur plaquette de silicium



## Résines

SU-8 2005  
Shibley 1805, 1818  
AZ 2020  
LOR



## Equipements

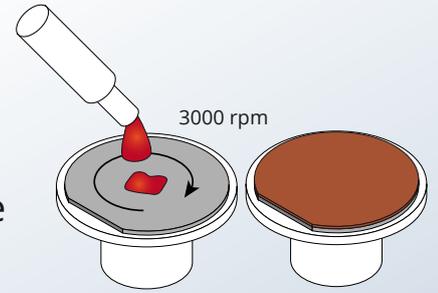


Karl Suss MJB4

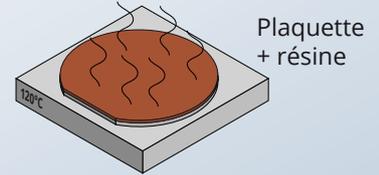


EVG 620

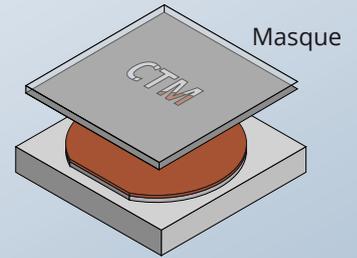
→ Enduction de résine à la tournette  
*Spincoating*



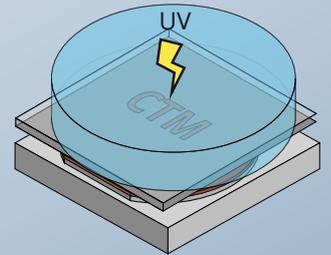
→ Recuit  
*Baking*



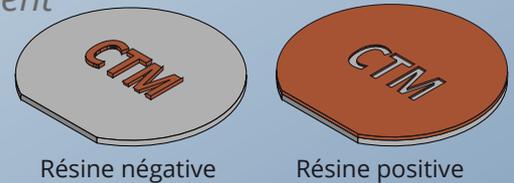
→ Alignement sous masque  
*Mask alignment*



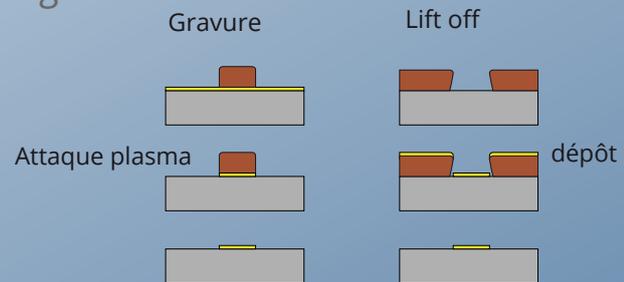
→ Exposition UV  
*UV exposure*



→ Développement  
*Development*



→ Gravure  
*Etching*



Centrale de Technologie  
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